reposition, some change may be made to capacitive sensing device **700**. For example, black chrome layers **706** and **712** would be patterned on the side closest to the repositioned user view **718**. As such, titanium layers **710** and **716** can be excluded since the chromium could act as the etch stop depending on the type of etchant used on the substantially transparent insulating layers **702** and **704**. Moreover, some chromium or tungsten may be deposited on the substantially transparent substrate to provide an adhesion layer for the aluminum layer **708**.

[**0064**] **FIG. 8** is a plan view of an exemplary capacitive sensing device **800** in accordance with an embodiment of the present invention. It is appreciated that capacitive sensing device **800** may have been manufactured utilizing the process represented by flowchart **200** of **FIG. 2** or flowchart **600** of **FIG. 6**. Specifically, capacitive sensing device **800** includes a substantially transparent substrate **802** having a first set of conductive traces **806** patterned thereon. Additionally, a second set of conductive traces **804** have been patterned above conductive traces **806** and substantially transparent substrate **802**. As such, the combination of conductive traces **804** and **806** form a sensing area **808** of capacitive sensing device **800**. Furthermore, conductive traces **804** and **806** are each coupled to sensing circuitry **810** that enables the operation of capacitive sensing device **800**. It is noted that capacitive sensing device **800** can be placed over an underlying image or an information display device (not shown). As such, a user would view the underlying image or information display by looking through sensing area **808** of capacitive sensing device **800** as shown.

[**0065**] **FIG. 9** is a cross sectional view of an exemplary capacitive sensing device **900** in accordance with another embodiment of the present invention. It is appreciated that capacitive sensing device **900** may have been manufactured utilizing the process represented by flowchart **200** of **FIG. 2** or flowchart **600** of **FIG. 6**. Specifically, a second set of conductive traces **906** of capacitive sensing device **900** have been patterned to provide local bridges that electrically couple particular traces of a first set of conductive traces **904**. As such, an insulating material **908** is utilized to support the local bridges of the second set of conductive traces **906** while electrically insulating the second set of conductive traces **906** from particular traces of the first set of conductive traces **904**.

[**0066**] Within **FIG. 9**, the capacitive sensing device **900** includes a substantially transparent substrate **902** having a first set of conductive traces **904** patterned thereon. A user view **910** represents the direction from which users can view the capacitive sensing device **900**. As such, an underlying image or an information display device (not shown) could be located behind the capacitive sensing device **900** facing the user view **910**. In this manner, a user would be viewing the underlying image or information display device through capacitive sensing device **900**. Within the present embodiment, capacitive sensing device **900** is separate from active components used to comprise the information display device.

[**0067**] **FIG. 10** is a top view of capacitive sensing device **900** of **FIG. 9** in accordance with an embodiment of the present invention. The conductive trace **906** of capacitive sensing device **900** provides a local bridge that electrically couples particular traces of the first set of conductive traces **904**. Notice that the insulating material **908** electrically insulates the conductive trace **906** that bridges over one or the conductive traces **904**. It is noted that insulating material **908** can be opaque if the size or shape of the area of coverage of insulating material **908** is such that the capacitive sensing device **900** does not have to be arranged with respect to an underlying image in order to avoid substantial deleterious obstruction of the underlying image by insulating material **908**. By fabricating the capacitive sensing device **900** in the manner shown in **FIGS. 9 and 10**, fabrication costs can be reduced since less insulating material **908** is utilized to insulate the first set of conductive traces **904** from the second set of conductive traces **906**. Additionally, the weight of the capacitive sensing device **900** can be reduced since less material is used during its fabrication.

[**0068**] The foregoing descriptions of specific embodiments of the present invention have been presented for purposes of illustration and description. They are not intended to be exhaustive or to limit the invention to the precise forms disclosed, and obviously many modifications and variations are possible in light of the above teaching. The embodiments were chosen and described in order to best explain the principles of the invention and its practical application, to thereby enable others skilled in the art to best utilize the invention and various embodiments with various modifications as are suited to the particular use contemplated. It is intended that the scope of the invention be defined by the claims appended hereto and their equivalents.

What is claimed is:

1. A capacitive sensing device comprising:

a substantially transparent substrate; and

a first set of patterned conductive traces formed above said substantially transparent substrate, each of said first set of patterned conductive traces having a width such that said capacitive sensing device does not have to be arranged with respect to an underlying image in order to avoid deleterious obstruction of said underlying image by said first set of patterned conductive traces, said underlying image is separate from said capacitive sensing device, wherein said capacitive sensing device is separate from active components used to comprise an information display device.

2. The capacitive sensing device as described in claim 1, further comprising:

a second set of patterned conductive traces formed and coupled to said substantially transparent substrate.

3. The capacitive sensing device as described in claim 2, wherein each of said second set of patterned conductive traces has a width such that said capacitive sensing device does not have to be arranged with respect to an underlying image in order to avoid deleterious obstruction of said underlying image by said second set of patterned conductive traces.

4. The capacitive sensing device as described in claim 2, further comprising:

an insulating material coupled between said first set of patterned conductive traces and said second set of patterned conductive traces.

5. The capacitive sensing device as described in claim 4, wherein said insulating material is substantially transparent.